

ABSTRACT

A method is disclosed for forming an array of focusing elements for use in a lithography system. In accordance with an embodiment, the method includes the steps of providing a master element that includes at least one diffractive pattern at a first location with respect to a target surface, illuminating the master element to produce a first diffractive pattern on the target surface at the first location, moving the master element with respect to the target surface to a second location with respect to the target surface, and illuminating the master element to produce a second diffractive pattern on the target surface at the second location.